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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/813,913	03/30/2004	Jisoo Kim	LMRX-P036/P1213	LMRX-P036/P1213 5070	
32986 7	12/07/2004		EXAM	EXAMINER	
IPSG, P.C.			PERT, EVAN T		
P.O. BOX 700	640				
SAN JOSE, CA 95170-0640			ART UNIT	PAPER NUMBER	
·			2829		
			DATE MAIL ED 10/07/200	DATE MAIL ED. 12/07/2004	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Annlie	notion No.	Applicant(a)				
Office Action Summary		cation No.	Applicant(s)				
		3,913	KIM ET AL.				
Onice Action Summary	Exam		Art Unit				
T. 11411 NO 24TE 641	Evan		2829				
The MAILING DATE of this comm Period for Reply	unication appears on	the cover sheet with the	correspondence address				
A SHORTENED STATUTORY PERIOD THE MAILING DATE OF THIS COMMU - Extensions of time may be available under the provisi after SIX (6) MONTHS from the mailing date of this co - If the period for reply specified above is less than thirt - If NO period for reply is specified above, the maximun - Failure to reply within the set or extended period for re Any reply received by the Office later than three mont earned patent term adjustment. See 37 CFR 1.704(b)	INICATION. ons of 37 CFR 1.136(a). In nommunication. y (30) days, a reply within the notation will apply a sply will, by statute, cause the his after the mailing date of the	to event, however, may a reply be a statutory minimum of thirty (30) d and will expire SIX (6) MONTHS from a application to become ABANDON	timely filed  ays will be considered timely.  m the mailing date of this communication.  NED (35 U.S.C. § 133).				
Status							
1) Responsive to communication(s)	filed on <i>30 March 20</i>	004					
2a)☐ This action is <b>FINAL</b> .	2b)⊠ This action						
3) Since this application is in condition							
Disposition of Claims			,				
4) ⊠ Claim(s) <u>1-40</u> is/are pending in the 4a) Of the above claim(s) is 5) □ Claim(s) is/are allowed. 6) □ Claim(s) is/are rejected. 7) ⊠ Claim(s) <u>1-40</u> is/are objected to. 8) □ Claim(s) are subject to res	s/are withdrawn from						
Application Papers							
9)⊠ The specification is objected to by 10)⊠ The drawing(s) filed on 30 March 2 Applicant may not request that any ol Replacement drawing sheet(s) includ 11)□ The oath or declaration is objected	2004 is/are: a) ☐ ac ojection to the drawing- ing the correction is re	(s) be held in abeyance. Squired if the drawing(s) is c	ee 37 CFR 1.85(a). objected to. See 37 CFR 1.121(d).				
Priority under 35 U.S.C. § 119							
12) Acknowledgment is made of a claim  a) All b) Some * c) None of  1. Certified copies of the prior  2. Certified copies of the prior  3. Copies of the certified copies  application from the Internative See the attached detailed Office accepted.	: ity documents have ity documents have es of the priority doc tional Bureau (PCT	been received. been received in Applica uments have been recei Rule 17.2(a)).	ation No ved in this National Stage				
Attach manufa)	•						
Attachment(s)  1) Notice of References Cited (PTO-892)		4) Intention Summa	n/ (PTO-413)				
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) Paper No(s)/Mail Date							
Information Disclosure Statement(s) (PTO-1449     Paper No(s)/Mail Date		5) Notice of Informa 6) Other:	Patent Application (PTO-152)				

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#### **DETAILED ACTION**

### **Drawings**

1. The drawings are non-compliant with 37 CFR 1.84(p)(3), which states that all lettering and numbering in drawing "must" measure minimum 1/8 inch height.

Furthermore, Step 708 in Fig. 7, reading "is present is the contact" should seemingly read --is present in the contact opening-- (for example, see [0067], last sentence in view of Fig. 5).

New drawings are required.

#### Specification

2. The specification is objected to for informalities:

At [0001], "methods and apparatus methods and apparatus" is redundant.

At [0003], last sentence "Appropriate etchant source are then flowed..." is not grammatically correct.

At [0028] and [0029], the phrase "is present is the contact after the exposing" should seemingly read --is present in the contact opening after the exposing-- (for example, see [0067], last sentence in view of Fig. 5).

Correction is required.

## Claim Objections

3. Claims 1-40 are objected to because of informalities in the independent claims:

In claims 1 and 21, the phrase "is present is said contact after said exposing" should seemingly read --is present in said contact opening after said exposing-- (for example, see [0067], last sentence in view of Fig. 5).

In claims 1 and 21, 2nd line, the phrase "contact reaches" should read --contact opening reaches--, for better grammatical clarity.

Appropriate correction is required.

#### Allowable Subject Matter

- 4. Claims 1-40 are objected to for informalities in the base claims, but are otherwise allowable.
- 5. The following is a statement of reasons for the indication of allowable subject matter:

While the prior art discloses methodologies involving detection of an etching endpoint by detecting metal chloride, the prior art does not suggest or disclose detection of
metal chloride "in a contact opening" for determining an end-point of etching a contact
opening (with plasma) to reach an underlying metal layer, wherein the underlying metal
layer generates the metal chloride when the etching of the contact opening reaches
through to the underlying metal layer.

As seen in Fig. 5, detection of metal chloride can provide a meaningful assessment of a contact opening etched to reach an underlying metal layer.

#### Conclusion

6. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Burns et al. (US 4,687,539) discloses the detection of copper chloride of determining an etching end-point of a contact window using a laser etching operation, but does not suggest applying the method to etching with plasma.

Klippert II et al. (US6,136,712) teaches the prior art problem of determining etching end-point in etching contact openings over metal contacts.

US 2001/0023991 A1, US 5,312,515, US 5,200,032, JP 4-106921, JP 2-172224, US 4,675,072, and US 4,289,188 disclose detecting etching end-points by detecting metal chloride, but these references detect a falling off of concentration to detect when a layer has been etched away, in contrast to applicant's claimed invention where the detection of a rise in concentration of metal chloride in a contact opening indicates that a contact opening has been etched through to reach an underlying metal contact layer.

7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Evan Pert whose telephone number is 571-272-1969. The examiner can normally be reached on M-F (7:30AM-3:30 PM).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Tokar can be reached on 571-272-1812. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

EVAN PERT PRIMARY EXAMINER

ETP November 29, 2004